

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Koichi WATANABE et al.

Title: SPUTTERING TARGET AND PROCESS FOR PRODUCING Si OXIDE FILM THEREWITH

Appl. No.: 10/573,406

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Examiner: Jason Berman

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LETTER REGARDING SUPPLEMENTAL NOTICE OF ALLOWABILITY

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

Applicants note that claim 13 is not shown correctly in the Supplemental Notice of Allowability and should read as:

13. The process for producing an Si oxide film according to claim 12, wherein the Si oxide film is an optical thin film.

Respectfully submitted,

By

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